## Application No. 10/564791 INFORMATION DISCLOSURE Filing Date January 13, 2006 First Named Inventor Takada et al. STATEMENT BY APPLICANT Art Unit 1742 (Multiple sheets used when necessary) Examiner Piery, Michael SHIGA3.008APC SHEET 1 OF 1 Attorney Docket No.

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Examiner Initials	Cite No.	Document Number <i>Number - Kind Code (if known)</i> Example: 1,234,567 B1	Publication Date MM-DD-YYYY	Name of Patentee or Applicant	Pages, Columns, Lines Where Relevant Passages or Relevant Figures Appear					
/M.P./	1	5,373,026	12-1994	Bartz et al.						
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	NON PATENT LITERATURE DOCUMENTS							
Examiner Initials	Cite No.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T <sup>1</sup>					
/M.P./	3	LIU et al., "Preparation and Characterization of Copolymers Containing (+)-Bornyl Methacrylate and Their Racemate for Positive-Tone Photoresist," <i>J. Appl. Polym. Sciences</i> , 81:3538-3544, (2001)						
/M.P./	4	FEDYNYSHYN, et al. "Contribution of Photoacid Generators To Material Roughness," <i>J. Vac. Sci. Technology</i> , B24(6), 3031-3039, (2006)						
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Examiner Signature /Michael Piery/ Date Considered 10/09/2011

<sup>\*</sup>Examiner: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.